



Attorney Docket No. SEL 239

April 8, 2004

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:	
Tomshimitsu KONUMA et al	) I hereby certify that this correspondence ) is being deposited with the United States Postal Service as first class mail in an
Serial No.: 09/782,239	envelope addressed to: Commissioner for Patents, P.O. Box 1450,
Filed: February 13, 2001	) Alexandria, VA 22313-1450, on April; 8, 2004
Art Unit: 2814	? Criatia m. nol
Examiner: Douglas A. Wille	
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# SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

For: SELF-LIGHT-EMITTING DEVICE AND

METHOD OF MANUFACTURING THE SAME

Dear Sir:

Pursuant to 37 C.F.R. §1.97, as revised on February 4, 1992, 1135 OG 23-24, Applicant hereby calls the Examiner's attention to documents listed on the attached form, which documents may be material to the examination of this application. Copies of the references are enclosed herewith for the Examiner's consideration.

No inference should be drawn that the attached list sets forth a comprehensive investigation of the prior art, that any or all are pertinent to the invention, or that any apparatus disclosed is equivalent to the subject invention.

The citation of the above-discussed documents is not to be construed as an assertion that more pertinent art could not

possibly be in existence. Citation of any document herein is not to be construed as an admission that any subject matter disclosed in the document is necessarily within the inventive field of endeavor, that any disclosure is necessarily prior in time to a particular date which may be relevant to the instant patent application, and/or that any disclosure is otherwise necessarily prior art with respect to the instant invention.

Applicant also respectfully reserves the right to later set forth how the instant invention is distinguished over the disclosure of any document or other art, including the disclosure of those documents discussed herein, that may be cited by the Examiner in rejecting a claim in the instant patent application.

As a RCE was filed no fee is believed necessary. If a fee is required, please charge Deposit Account No. 50/1039.

Respectfully submitted,

Mark J Murphy

Registration No: 34,225

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LIST OF PUBLICATIONS CITED BY APPLICANT

Atty Docket No. SEL 239	<u>Serial No.</u> 09/782,239
Applicant Toshimitsu KONUMA et al	
<u>Filing Date</u>	Group

2814

### U.S. PATENT DOCUMENTS

February 13, 2001

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE
	5,895,228	04/20/99	Biebuyck et al	438	99	03/20/97

#### FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	APPLICANT	English Abstract	English Trans.	FILING DATE
JP 07-258410 EP 0 768 352 EP 0 881 668 A2 EP 0 893 485 EP 0 899 987	10/09/95 04/16/97 12/02/98 01/27/99 03/03/99	UBE Ind. Ltd. Hitachi Chem Co. Dow Corning Toray Silicone Co. Ltd. Sumitomo Chem Co. TDK Corp.	. X		03/18/94 06/30/95 05/27/98 07/22/98 08/28/98

### OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

(Include name of author (in CAPITAL LETTERS), title of article or item (book, magazine, journal, serial, symposium, catalog, etc.) date, pages(s), volume-issue number(s), publisher, city and/or country where published).

- 1) European Search Report re application no. EP 03 02 0964, mailed December 3, 2003.
- 2) FRITSCH, U. et al, "A Submicron CMOS Two Level Metal Process with Planarization Techniques," V-MIC Conf., June 13-14, 1988 IEEE, pp. 69-75 (1988).
- 3) IBARAKI, N. et al, "A New a-Si TFT with SiO2/SiNx Gate Insulator for 10.4 inch LCDs," Proceedings of the International Display Research Conference, IEEE, pp. 97-100, (1991).
- 4) PRAMANIK, D. et al, "A High Reliability Triple Metal Process for High Performance Application Specific Circuits," VLSI Multilevel Interconnection Conference, June 11-12, 1991, pp. 27-33, (1991).

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DATE CONSIDERED:

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP form. Draw line through citation if not in conformance and not considered. Include a copy of this form with the next communication to applicant.